

TSMC-99-287



January 3, 2000

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To: Commissioner of Patents and Trademarks  
Washington, D.C. 20231

RECEIVED

Fr: George O. Saile, Reg. No. 19,572  
20 McIntosh Drive  
Poughkeepsie, N.Y. 12603

JAN 27 2000

TECHNOLOGY CENTER 2800

Subject:

Serial No. 09/434,563 11/12/99

H.J. Tao, H.J. Lin, F.C. Chen

METHOD TO CONTROL GATE CD

Grp. Art Unit: 2825

INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation  
In An Application.

The following Patents and/or Publications are submitted to  
comply with the duty of disclosure under CFR 1.97-1.99 and  
37 CFR 1.56. Copies of each document is included herewith.

RECEIVED  
1780 MAIL ROOM  
MAR - 6 2000

U.S. Patent 5,913,102 to Yang, "Method for Forming  
Patterned Photoresist Layers with Enhanced Critical Dimension  
Uniformity", discloses a system for controlling CD using a  
measurement parameter and a control parameter.

U.S. Patent 5,674,409 to Muller, "Nanolithographic Method  
of Forming Fine Lines", discloses a photoresist trimming  
process that uses ashing.

U.S. Patent 5,057,187 to Shinagawa et al., "Ashing Method for Removing an Organic Film on a Substance of a Semiconductor Device Under Fabrication", discloses a method of controlling an ashing process

U.S. Patent 4,717,445 to Leung, "Etch Bias Monitoring Technique", discloses an etch bias monitoring technique.

U.S. Patent 5,804,460 to Bindell et al., "Linewidth Metrology of Integrated Circuit Structures", discloses a method for measuring photoresist line widths.

Sincerely,



Stephen B. Ackerman,  
Reg. No. 37661